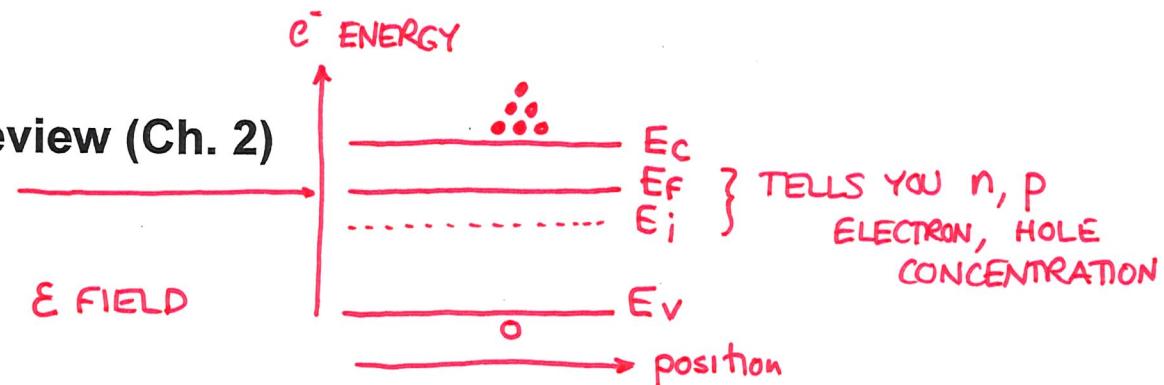


# ECE4904 Lecture 3

**Energy Band Diagram Review (Ch. 2)**  
 $E_F$  flat in equilibrium

**Carrier Motion: Drift (3.1)**  $E$  FIELD  
Drift Current (3.1.2)  
Mobility (3.1.3)  
Resistivity (3.1.4)

**Carrier Motion: Diffusion (3.2)** CONCENTRATION GRADIENT  
Diffusion current (3.2.3)  
Diffusion Coefficient (3.2.4)



IN EQUILIBRIUM  
NONDEGENERATE

$$\left. \begin{aligned} n &= n_i e^{(E_f - E_i)/kT} \\ p &= n_i e^{(E_i - E_f)/kT} \end{aligned} \right\} np = n_i^2$$

"np PRODUCT  
RELATIONSHIP"

**Handouts**

1-minute Quiz  
Textbook Figures 3.4,5,7,8

**Hand In: HW 1**

**HW 2 (online)**

## ECE4904 "One Minute" Quiz: Energy Band Diagram

This quiz explores the relationship between carrier concentrations ( $n, p$ ), doping concentrations ( $N_A, N_D$ ), types of material (n-type, p-type, intrinsic), the energy band diagram, and the Fermi level  $E_F$ .

Each line in the table below describes a different sample of silicon semiconductor in equilibrium at  $T=300K$ . If the material is doped, it is doped uniformly and only one type of dopant (acceptor or donor) is used. Using the information provided in each line of the table, fill in the blanks in each of the other columns on each line.

Indicate the type of material:	Indicate the acceptor $N_A$ and donor $N_D$ concentrations		Indicate the hole $p$ and electron $n$ carrier concentrations		Draw the energy band diagram; indicate the Fermi level $E_F$ relative to the intrinsic Fermi level $E_i$ (with energy difference in eV)
n-TYPE p-TYPE INTRINSIC	DOPING		CARRIER CONC		ENERGY BAND DIAGRAM
	$N_A$	$N_D$	$p$	$n$	
n-TYPE p-TYPE INTRINSIC $n > n_i$	0	$1E+14$ atom/cm <sup>3</sup>	$1E+6$ /cm <sup>3</sup> $< n$	$1E+14$ /cm <sup>3</sup> $\frac{1E+20}{1E+6}$	

np PRODUCT RELATIONSHIP  $np = n_i^2$

$$n(1E+6) = (1E+10)^2 \Rightarrow n = 1E+14$$

$$n = n_i e^{(E_F - E_i)/kT}$$

$$\text{KNOWN } E_F - E_i = kT \ln \left( \frac{n}{n_i} \right)$$

$$0.0259 \text{ eV} \ln \left( \frac{1E+14}{1E+10} \right) = 0.239 \text{ eV}$$

	$N_A$	$N_D$	$p$	$n$	
p-TYPE $E_F < E_i$	$2.2E+13$	0	$2.2E+13$ /cm <sup>3</sup>	$4.5E+6$ /cm <sup>3</sup>	

$$np = (1E+10)^2$$

$$n = \frac{1E+20}{2.2E+13}$$

$$p = n_i e^{(E_i - E_F)/kT}$$

$$(1E+10) e^{(0.2 \text{ eV} / 0.0259 \text{ eV})}$$

$$p = 2.2E+13$$

n-TYPE p-TYPE INTRINSIC	DOPING		CARRIER CONC		ENERGY BAND DIAGRAM
	N <sub>A</sub>	N <sub>D</sub>	p	n	
N <sub>D</sub> >N <sub>A</sub> n-TYPE	0	5E+15 /cm <sup>3</sup>	2E+4	5E+15	

$$P = \frac{n_i^2}{n} = \frac{1E+10}{5E+15}$$

n TYPE:  $E_F > E_i$   
 $E_F - E_i = kT \ln \left( \frac{n}{n_i} \right) = .0259 \ln \left( \frac{5E+15}{1E+10} \right) = 0.34 \text{ eV}$

T=300K  
 $P=n_i \quad n=n_i$

INTRINSIC (NOT DOPED)	0	0	1E+10 /cm <sup>3</sup>	1E+10 /cm <sup>3</sup>	
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	N <sub>A</sub>	N <sub>D</sub>	P	n	
p-TYPE VERY HEAVILY DOPED DEGENERATE	5E+22 /cm <sup>3</sup>	0	5E+22	<del>n = n<sub>i</sub><sup>2</sup></del>	

~~$E_i - E_F = .0259 \ln \left( \frac{5E+22}{1E+10} \right) = 0.757 \text{ eV}$~~

## DRIFT

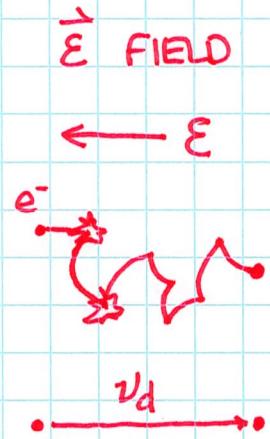
CARRIER IN SEMICONDUCTOR

NO  $\vec{E}$  FIELD



RANDOM COLLISIONS  
(THERMAL MOTION)  
ON AVERAGE:

NO NET MOTION

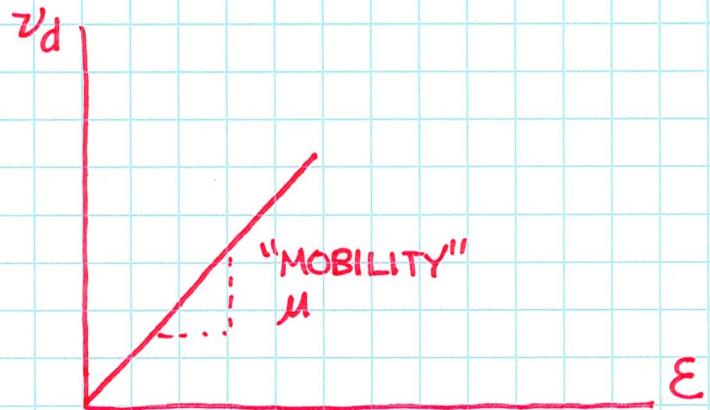


NET MOTION  
AVERAGE  
VELOCITY

$v_d$

"DRIFT  
VELOCITY"

PLOT  $v_d$  VELOCITY VS.  $E$  FIELD

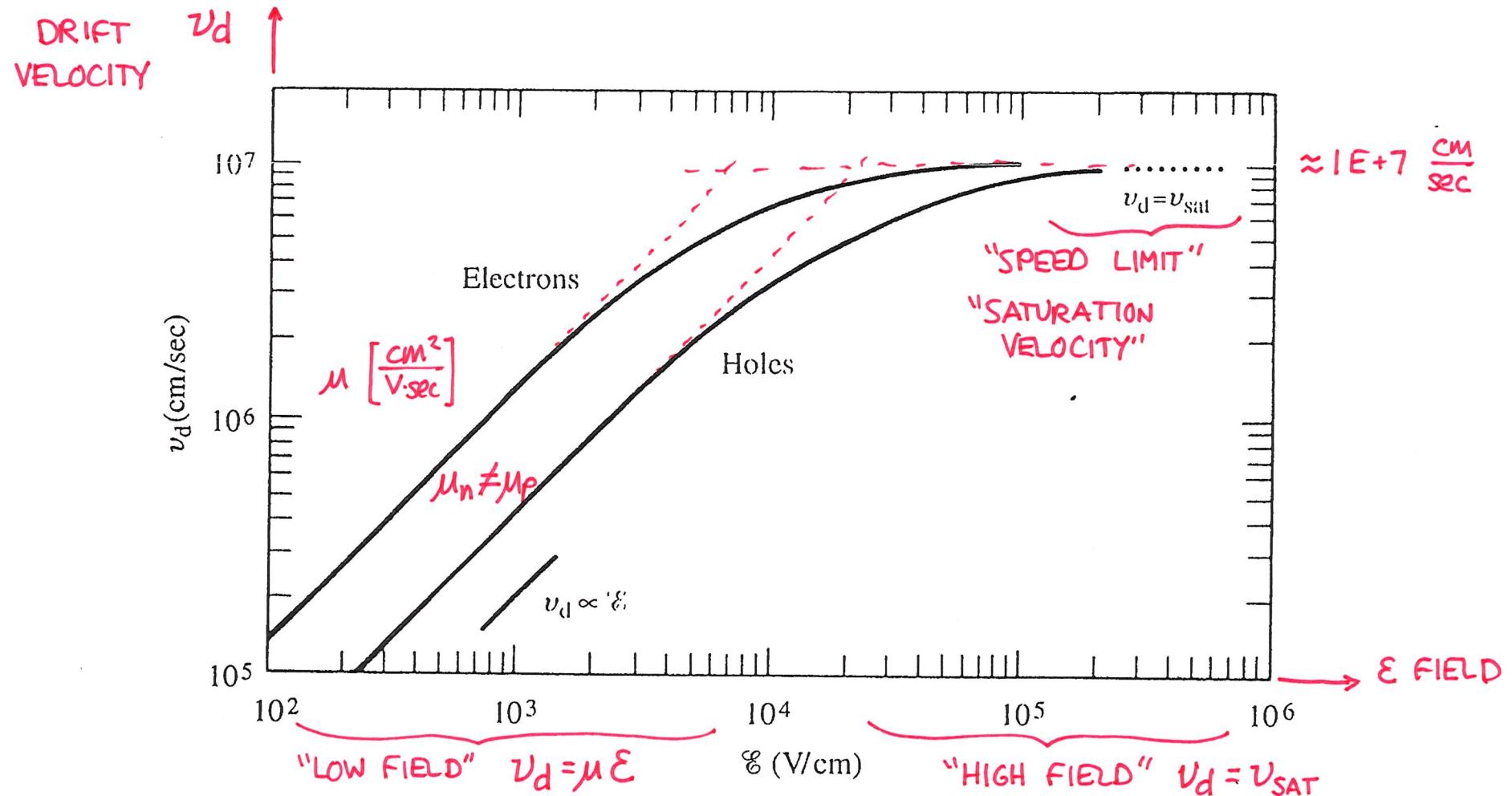


$$v_d = \mu E$$

$$\left[ \frac{\text{cm}}{\text{sec}} \right] \quad \left[ \frac{\text{cm}^2}{\text{V}\cdot\text{sec}} \right] \quad \left[ \frac{\text{V}}{\text{cm}} \right]$$

MOBILITY: AVERAGE EFFECT  
ON CARRIERS  
ALSO EXPERIENCING  
RANDOM THERMAL  
MOTION

## SEMICONDUCTOR FUNDAMENTALS



**Figure 3.4** Measured drift velocity of the carriers in ultrapure silicon maintained at room temperature as a function of the applied electric field. Constructed from the data fits and the data respectively in Jacoboni et al.<sup>[4]</sup> and Smith et al.<sup>[5]</sup>

MORE LATTICE COLLISIONS  
(DOPANT IMPURITY ATOMS)

### MOBILITY

$$\mu_n = 1360 \text{ cm}^2/\text{V}\cdot\text{s}$$

$$\mu_p = 460 \frac{\text{cm}^2}{\text{V}\cdot\text{s}}$$

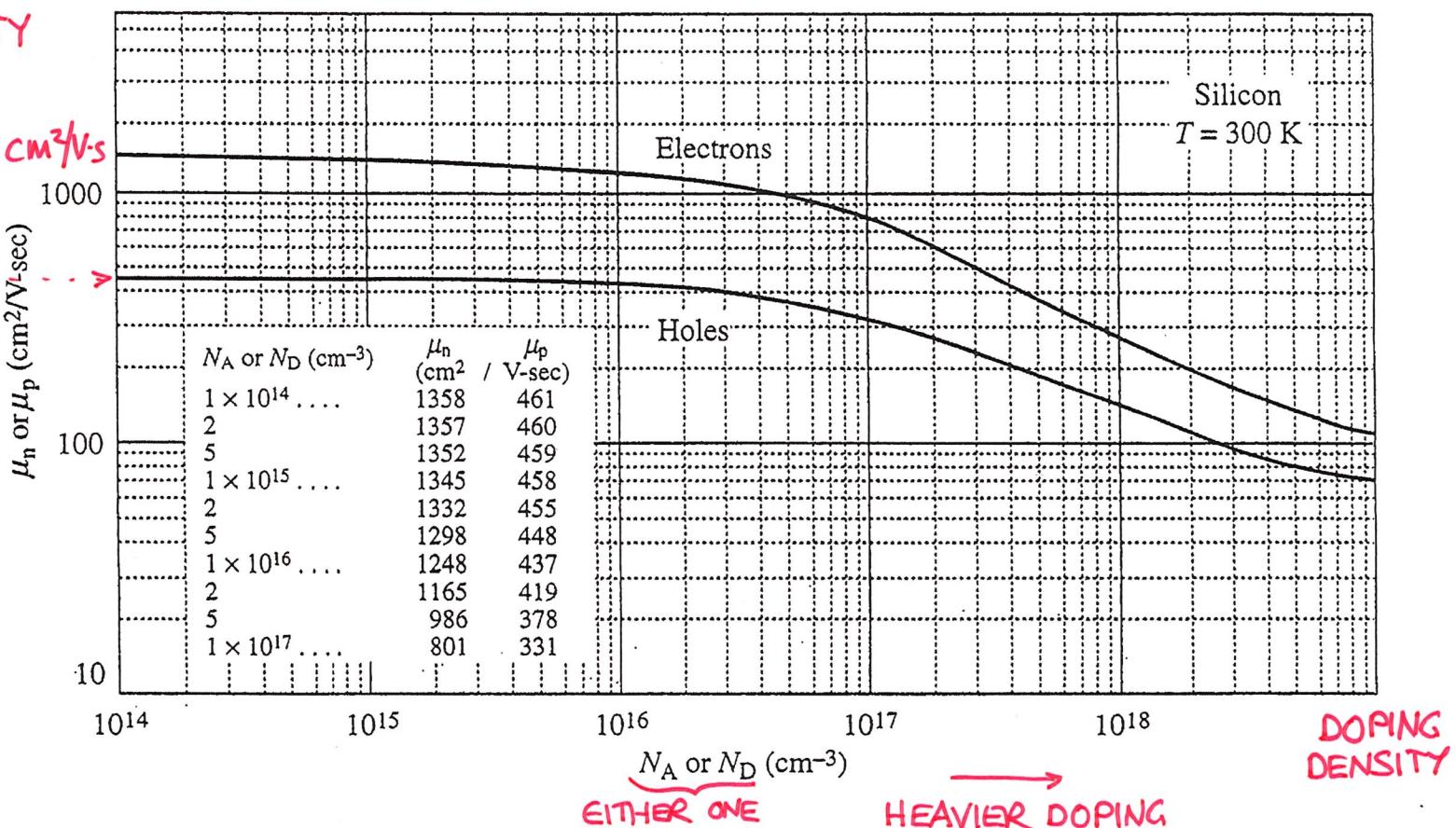
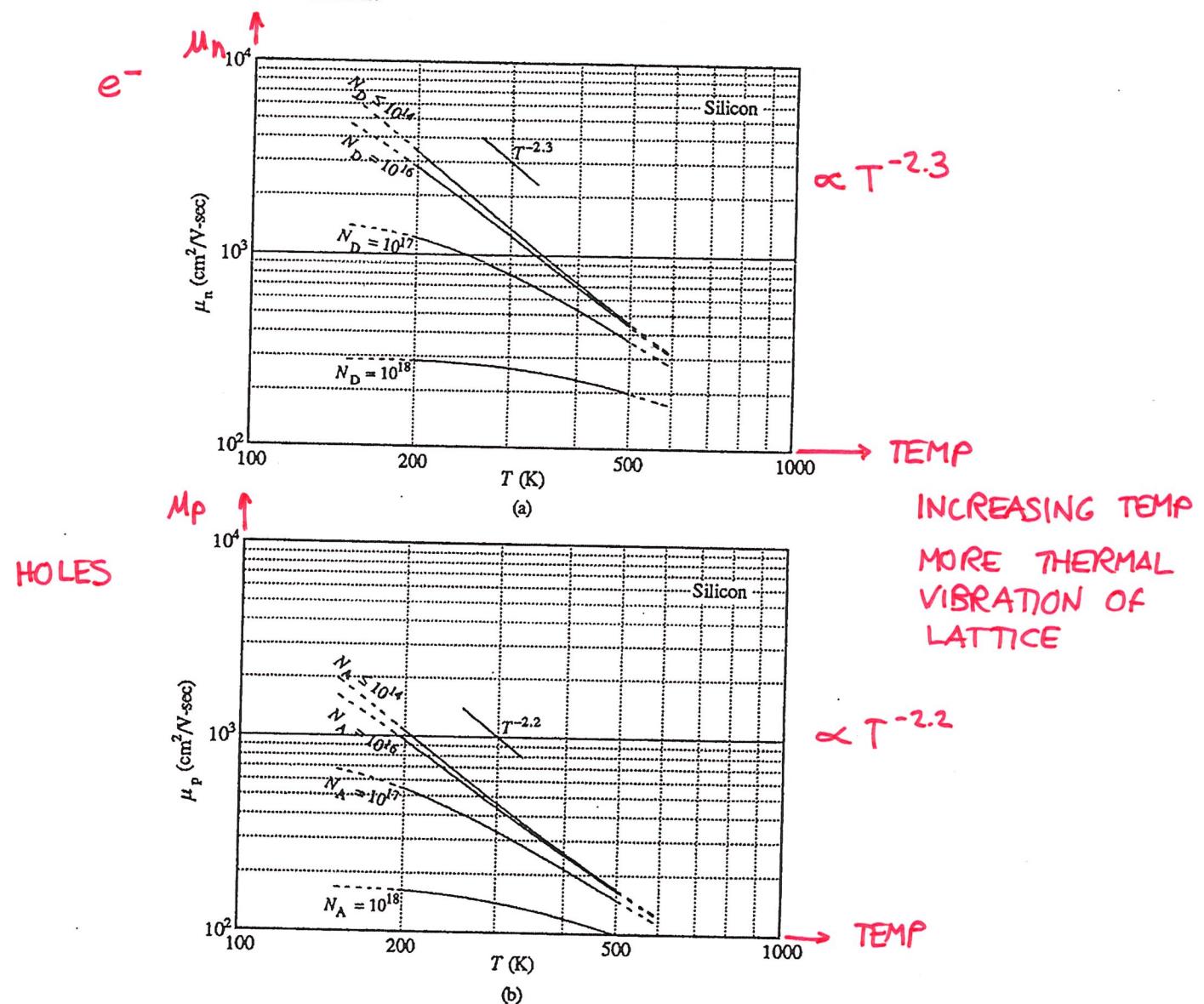


Figure 3.5 Room temperature carrier mobilities as a function of the dopant concentration in (a) Si

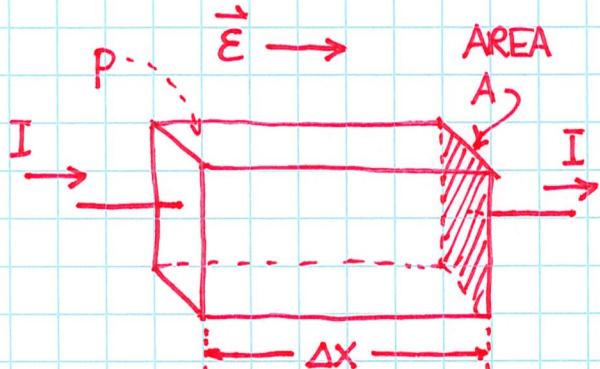


**Figure 3.7** Temperature dependence of (a) electron and (b) hole mobilities in silicon for dopings ranging from  $\leq 10^{14}/\text{cm}^3$  to  $10^{18}/\text{cm}^3$ . The curves were constructed using the empirical fit relationships and parameters presented in Exercise 3.1. The dashed line portion of the curves correspond to a slight extension of the fit beyond the verified  $200 \text{ K} \leq T \leq 500 \text{ K}$  range of validity.

CURRENT

FLOW OF CHARGE  
PER UNIT TIME

$$\frac{dQ}{dt}$$



DEFINITION

$$I = \frac{dQ}{dt} \xrightarrow{DC} \frac{\Delta Q}{\Delta t} \quad [1]$$

$\Delta Q$  ALL CHARGE IN VOLUME

$\Delta t$  TIME FOR ALL OF  $\Delta Q$  TO  
CROSS THROUGH  $\Delta A$

$p$  HOLES/cm<sup>3</sup> (UNIFORM)

$q$  e<sup>-</sup> CHARGE 1.6 E-19 coul

TOTAL CHARGE

$$\Delta Q = q \frac{p}{\text{CARRIER}} \frac{A \Delta x}{\text{VOL}} \quad [2]$$

DRIFT VELOCITY  
(ASSUME LOW FIELD)

$$v_d = \mu E \quad \star$$

FOR "LAST" CHARGE  
TO GET THROUGH A

$$v_d = \frac{\Delta x}{\Delta t} \Rightarrow \Delta t = \frac{\Delta x}{v_d} \quad [3]$$

SUB [2], [3] INTO [1]

$$I = \frac{q p A \Delta x v_d}{\Delta x} \quad [4]$$

$$I = q p A v_d$$

MORE SPECIFIC LABELING

$$I_{\text{p drift}} = q p A v_d \quad [4]$$

NORMALIZE CURRENT TO  
CROSS SECTIONAL AREA

$$J = \frac{I}{A} \quad \left. \begin{array}{l} \{ [A] \\ \{ [cm^2] \end{array} \right. \Rightarrow \left[ \frac{A}{cm^2} \right]$$

"CURRENT  
DENSITY"

$$I = JA$$

$$\vec{J}_{\text{p drift}} = q p \vec{v}_d \quad [5]$$

IN GENERAL  $\vec{J}$ ,  $\vec{v}$  VECTORS

LOW FIELD: USE  $\star$  IN [5]

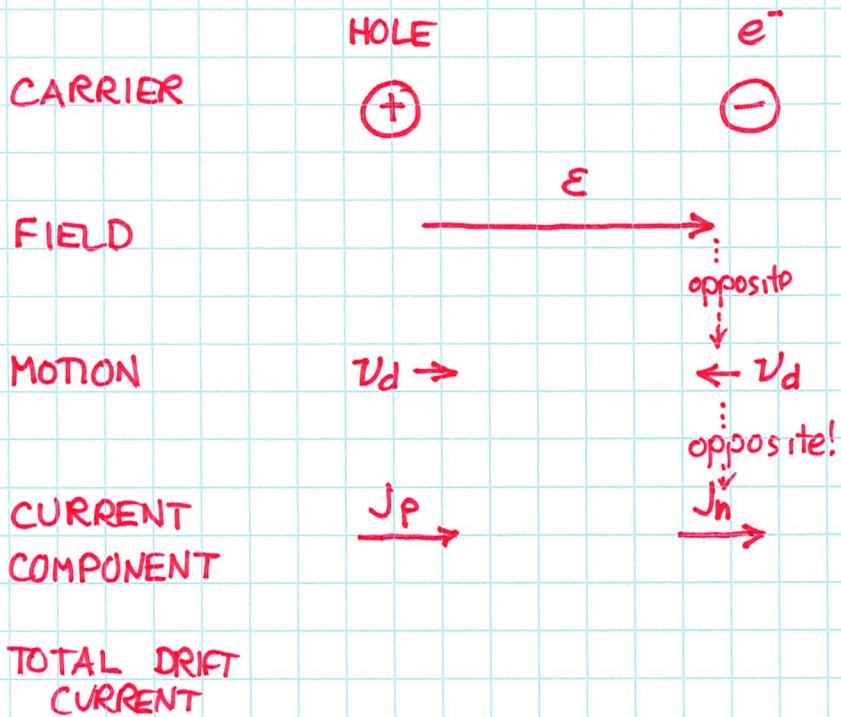
$$\underbrace{\vec{J}_{\text{p drift}}}_{\frac{A}{cm^2}} = \underbrace{q p \mu}_{\frac{1}{\rho}} \underbrace{\vec{E}}_{\frac{V}{cm}}$$

"OHM'S LAW FOR MATERIALS"

$$I = \frac{1}{R} V \quad \left. \begin{array}{l} \{ \\ \{ \end{array} \right. \text{CIRCUITS}$$

$[\rho]$  RESISTIVITY  
[ $\Omega \cdot \text{cm}$ ]

CURRENT DUE TO BOTH HOLES,  $e^-$



OHM'S LAW  $V = I R$

$E = J \rho \}$  RESISTIVITY

$$R = \rho \frac{l}{A}$$

} CURRENT COMPONENTS IN  
SAME DIRECTION AS  $E$  FIELD  
FOR BOTH HOLES,  $e^-$

TOTAL DRIFT CURRENT

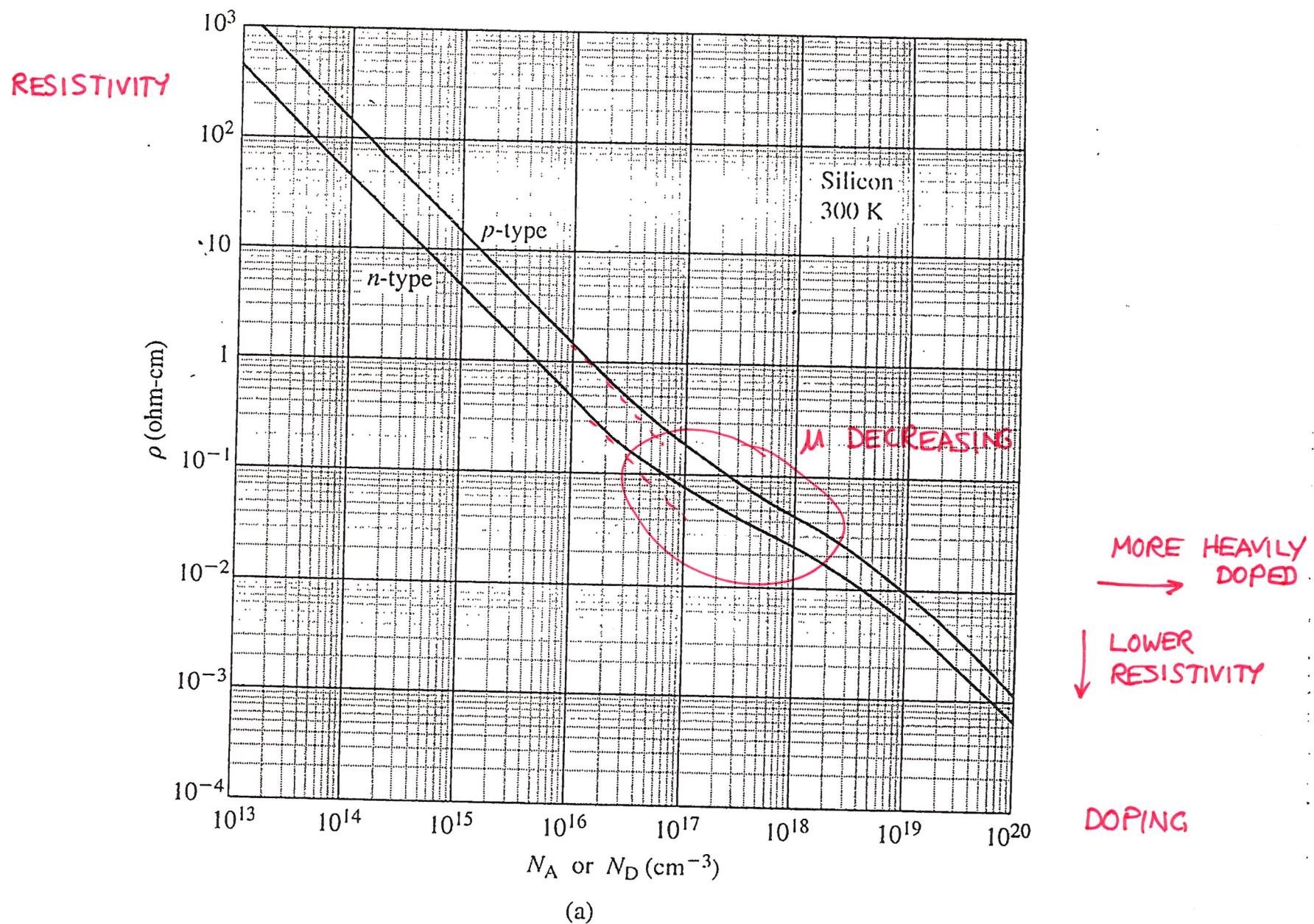
$$J_{\text{drift}} = J_{p\text{drift}} + J_{n\text{drift}}$$

$$= q \mu_p M_p E + q n \mu_n E$$

$$J_{\text{drift}} = \underbrace{q(\mu_p p + \mu_n n)}_{\frac{1}{\rho}} E$$

RESISTIVITY

$$\rho = \frac{1}{q(\mu_n n + \mu_p p)} \quad [\Omega \cdot \text{cm}]$$



**Figure 3.8** Resistivity versus impurity concentration at 300 K in (a) Si and (b) other semiconductors. [(b) From Sze<sup>[2]</sup>, © 1981 by John Wiley & Sons, Inc. Reprinted with permission.]

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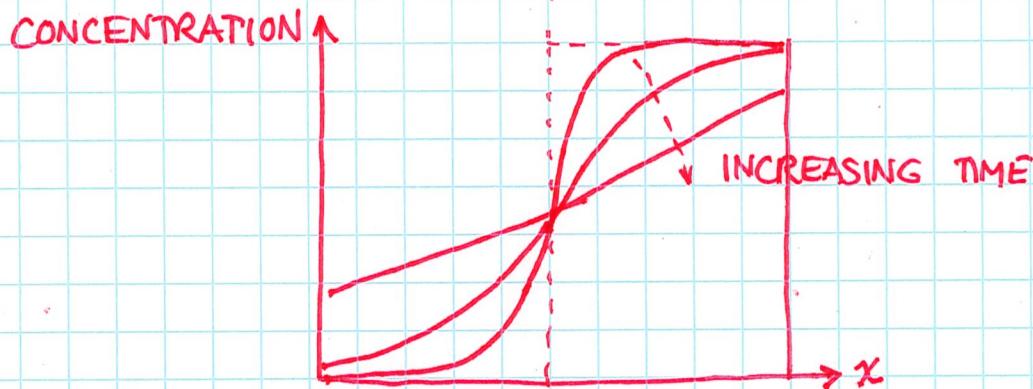
## DIFFUSION

GENERAL: APPLIES TO  
ANY MOBILE PARTICLES

+

CONCENTRATION  
GRADIENT

WILL BE "FLATTENED OUT" (REDUCED)  
OVER TIME BY RANDOM THERMAL MOTION



## DIFFUSION LAW

$$\underbrace{\dot{F}}_{\substack{\text{FLOW} \\ \text{PARTICLES/SEC} \\ \text{CM}^2}} = - D \underbrace{\nabla p(x)}_{\substack{\text{GRADIENT} \\ \frac{dp}{dx} \\ \text{SLOPE}}} \quad \text{NOT NECESSARILY UNIFORM! FUNCTION OF SPATIAL POSITION}$$

↑  
DIFFUSION COEFFICIENT

$$\left[ \frac{\text{cm}^2}{\text{sec}} \right]$$

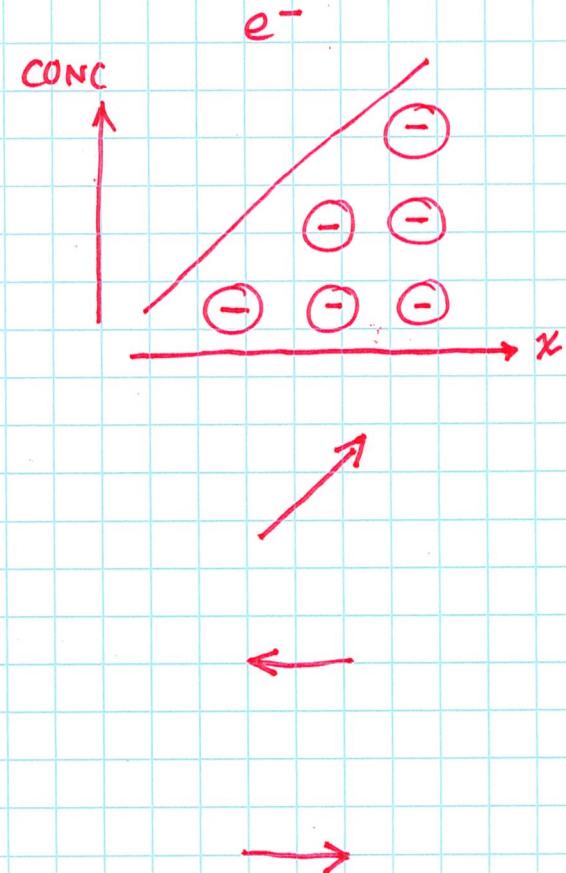
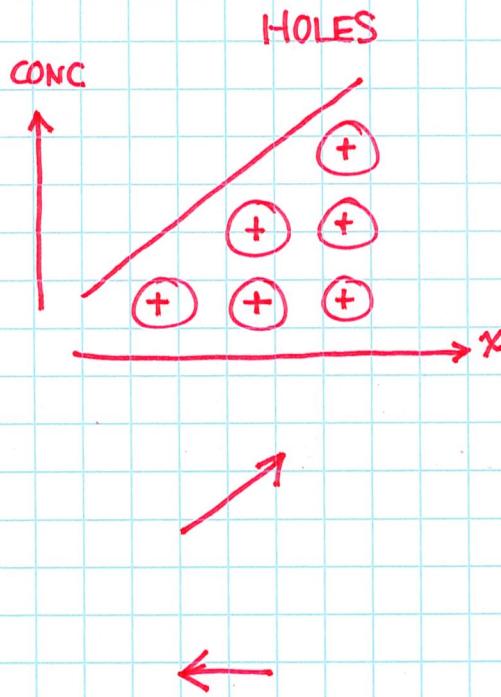
## DIFFUSION OF CHARGE CARRIERS

CARRIER CONCENTRATION

GRADIENT

FLOW DUE TO DIFFUSION

CURRENT DENSITY  $J$



$$J_{p|diff} = -q D_p \vec{\nabla} p$$

$$1D \quad J_{p|diff} = -q D_p \frac{dp}{dx}$$

$$J_{n|diff} = +q D_n \vec{\nabla} n$$

$$J_{n|diff} = +q D_n \frac{dn}{dx}$$

HOLE,  $e^-$   $J$  IN OPPOSITE DIRECTIONS!